

## INFORMATION DISCLOSURE STATEMENT

FORM PTO 1449 ( <i>modified</i> )  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  LIST OF REFERENCES CITED BY APPLICANT(S) ( <i>Use several sheets if necessary</i> )  Date Submitted to PTO: July 22, 2008			ATTY DOCKET NO. 2006_0772A	SERIAL NO. 10/581,256			
			APPLICANT Mitsuhiro OKUNE et al.				
			FILING DATE May 31, 2006	GROUP 1765			
U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA	5,871,659	2/1999	Sakano et al.			
	AB	4,214,946	7/1980	Forget et al.			
	AC						
	AD						
	AE						
	AF						
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
	BA						
	BB						
	BC						
	BD						
	BE						
OTHER DOCUMENT(S) ( <i>Including Author, Title, Date, Pertinent Pages, Etc.</i> )							
	CA	Supplementary European Search Report issued <u>June 11, 2008</u> in EP 04 81 9793, which is a foreign counterpart to the present application					
	CB	Meint J. DE BOER et al., "Guidelines for Etching Silicon MEMS Structures Using Fluorine High-Density Plasmas at Cryogenic Temperatures", JOURNAL OF MICROELECTROMECHANICAL SYSTEMS IEEE Service Center, Piscataway, NJ, vol. 11, no. 4, August 1, 2002 (8/1/2002)					
	CC	Seiji SAMUKAWA et al., "Effects of Discharge Frequency in Plasma Etching for Ultra large-Frequency Plasma Source for High-Performance Etching for Ultra large-Scale Integrated Circuits", JAPANESE JOURNAL OF APPLIED PHYSICS, Japan, Society of Applied Physics, Tokyo, Japan, vol. 39, no. 4A, Part 01, April 1, 2000 (4/1/2001)					
	CD						
EXAMINER	/Mahmoud Dahimene/			DATE CONSIDERED	07/28/2008		

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /M.D./